

MR-30028 – Precision Wafer Rotation Stage

The [SMARSHIFT](#) MR-30028 rotational stage is a large-area rotator with a diameter of 300 mm and a large aperture of 110 mm. It features high speed, high torque and long lifetime at uncompromising precision. Its compact footprint and low profile simplifies integration into existing systems and leaves enough space for your application.



Applications

The MR-30028 rotator has been specifically designed as a wafer rotation stage. As a platform for up to 300 mm (12") wafers, it can be used for metrology methods (such as reflectometry, reflection spectroscopy, spectroscopic ellipsometry (VASE), and others) or for manufacturing (for wafer bonding, EUV lithography, and others). Additional application areas include optical alignment of heavier objects in photonics industry and astronomy.

Travel: ∞ Dimensions (mm): 300 × 28 Weight: 5 kg

	Mechanical
Travel [°]	∞
Max. Normal Force [N]	1000
Dimensions [mm]	300 × 28
Weight [g]	5000
Aperture [mm]	110
	Material
Base Material	Aluminum, black anodized
	Open-loop
Angular Velocity [°/s]	540
	Closed-Loop
Sensor Types	S
Sensor Resolution [μ°]	<1
Angular Velocity [°/s]	540